

Ru-Si (Ruthenium-Silicon)

H. Okamoto

In this Supplemental Literature Review section, [2002Oka] showed the Ru-Si diagram thermodynamically assessed by [2001Du] and by [2001Liu]. The diagrams obtained by these authors were similar. The diagram of [2001Liu] is shown in Fig. 1. Since then, [2002Iva] discovered by DTA a new phase, RuSi_2 , forming peritectoidally at 962 °C, as shown with dashed lines in Fig. 1.

References

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2002Iva: L. Ivanenko, G. Behr, C.R. Spinella, and V.E. Borisenko, RuSi_2 : Evidence of a New Binary Phase in the Ruthenium-Silicon System, *J. Cryst. Growth*, 2002, **236**, p 572-576

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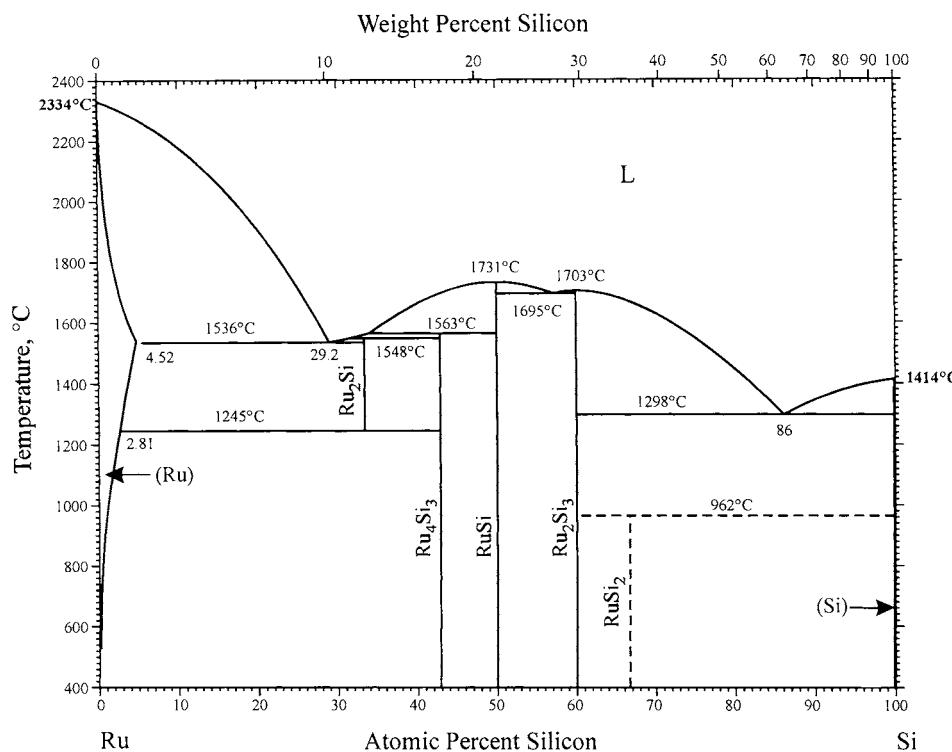


Fig. 1 Ru-Si phase diagram